

IN THE CLAIMS

Claims 1-24 (canceled)

25. (new) A coating for a substrate comprising a transparent Si_3N_4 or SiN_x layer directly on the substrate, a semimetallic layer above the Si_3N_4 or SiN_x layer and with a further Si_3N_4 or SiN_x layer as well as with a dielectric oxide layer selected from the group consisting of Al_2O_3 , SnO , Nb_2O_5 , TiO_2 and SiO_2 , wherein the dielectric oxide layer is disposed on the semimetallic layer and the further Si_3N_4 layer on the dielectric oxide layer.

26. (new) The coating for a substrate as claimed in claim 25, wherein the semimetallic layer comprises a CrN layer.

27. (new) The coating for a substrate as claimed in claim 25, wherein a dielectric oxide layer is provided between the transparent Si_3N_4 or SiN_x layer and the semimetallic layer.

28. (new) The coating for a substrate as claimed in claim 25, wherein x is a number smaller than 4/3.

29. (new) The coating for a substrate as claimed in claim 26, wherein the semimetallic layer comprises NiCrN or NiCrO_x .

30. (new) A coating for a substrate as claimed in claim 25, wherein the transparent Si_3N_4 or substoichiometric SiN_x layers have each a layer thickness of 20 to 120 nm.

31. (new) A coating for a substrate as claimed in claim 25, wherein the dielectric oxide layers have each a layer thickness of 4 to 120 nm.

32. (new) A coating for a substrate as claimed in claim 25, wherein the semimetallic NiCrN, CrN or NiCrO_x layers have a layer thickness of 5 to 40 nm.

33. (new) A coating for a substrate as claimed in claim 25, wherein said substrate is glass.

34. (new) A coating for a substrate as claimed in claim 25, wherein said substrate is a synthetic material.

35. (new) A coating for a substrate as claimed in claim 25, further comprising additional layers comprising Cr, Ni or NiCr.